Form PTO-1449 (Rev. 2-32)	Patent & Trademark Office		Atty. Docket No. Q59993	Serial N	Serial No.		
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)			Applicant: Isao AMEMIYA				
			Filing Date: June 30, 2000	Group:			
		U.S. PAT	ENT DOCUMENTS				
Examiner Initial	Document Number	Date	Name	Class	Sub- Class	Filing Date (if appropriate)	
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		FOREIGN PA	TENT DOCUMENTS				
	Document	Date	Country	Class	Sub-	Translation	
20/2	10.001404				class	Yes/No	
	10-321495	12/4/98	JAPAN			NO	
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7	S.D. Berger et al, "New Approach to Projection-Electron Lithography with Demonstrated 0.1 µm Linewidth", Appl. Phys. Letter, 57(2), 9, July 1990, pp. 153						
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AMDIED: >	111/1/ #D/-						
AMINER:	Max All		DATE CONSIDERE	D: 9/C/03			
XAMINER: Initia	al if citation considered, who	ether or not cit	ation is in conformance	with MPFP 6	09; draw lin	ne through citation	